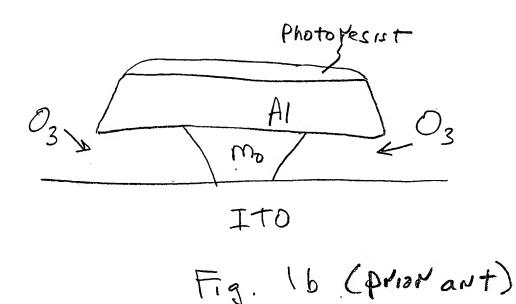


Fig. la (Prior art)



## Etch rate of Materials by O3 water (85ppm, pH3.3)

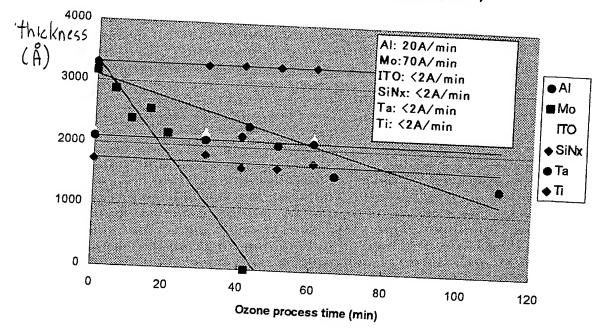
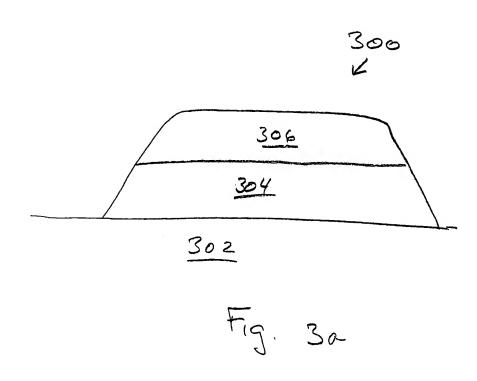
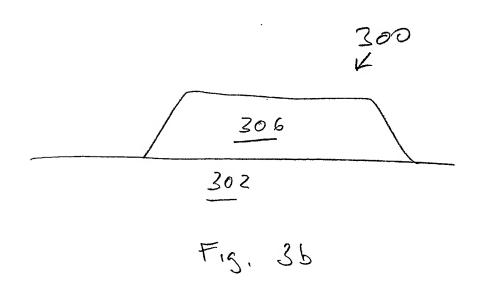


Fig. 2





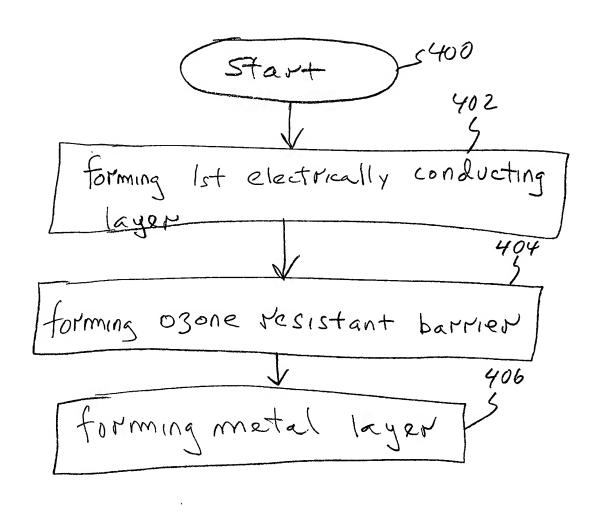


Fig. 4

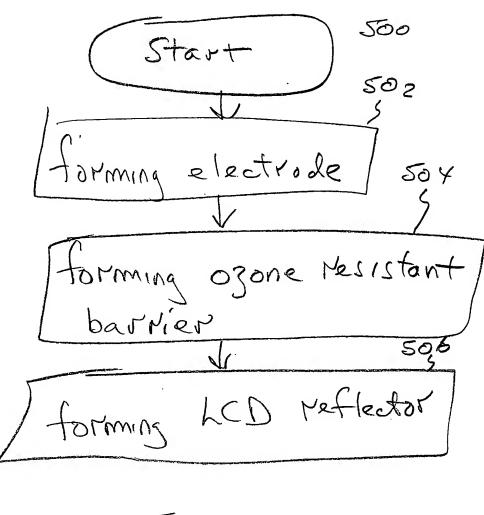


Fig. 5

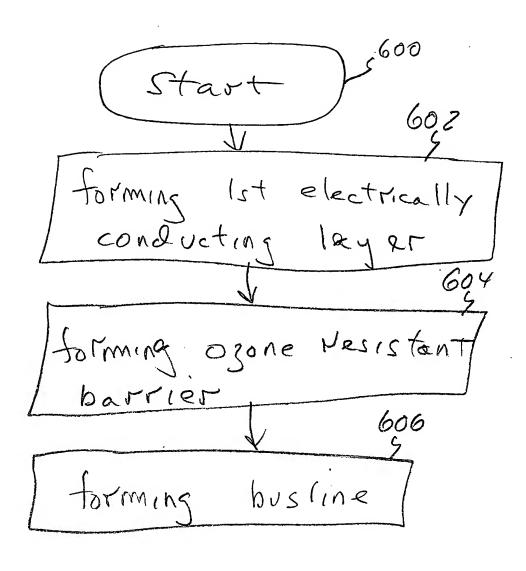


Fig. 6

STATT electrically Ozone resistant barrier orming metal 708 Pattern 2 noto resist Primare meta etching photo resist Stripping LCD reflector leaving Fig. 7

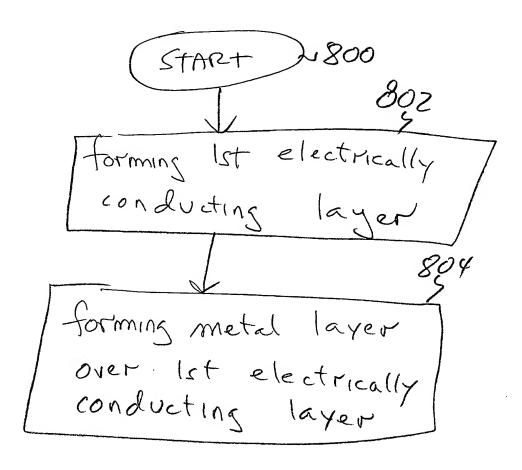


Fig. 8